

Supporting Information

Facile Fabrication and Enhanced Photocatalytic Performance of Ag/AgCl/rGO Heterostructure Photocatalyst

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Figure S1:

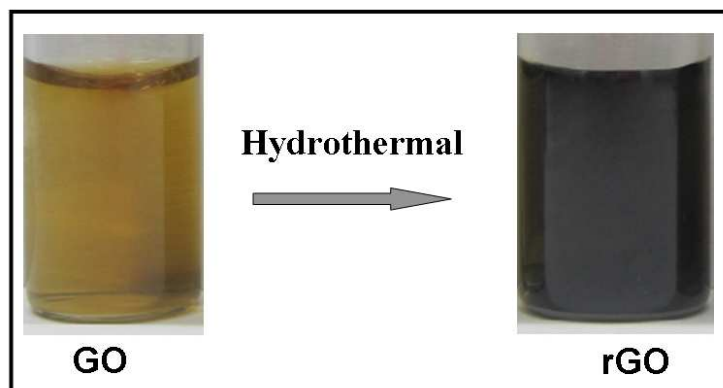


Figure S1 The photographs of GO solution (left) before and (right) after hydrothermal treatment at 130°C

Figure S2:

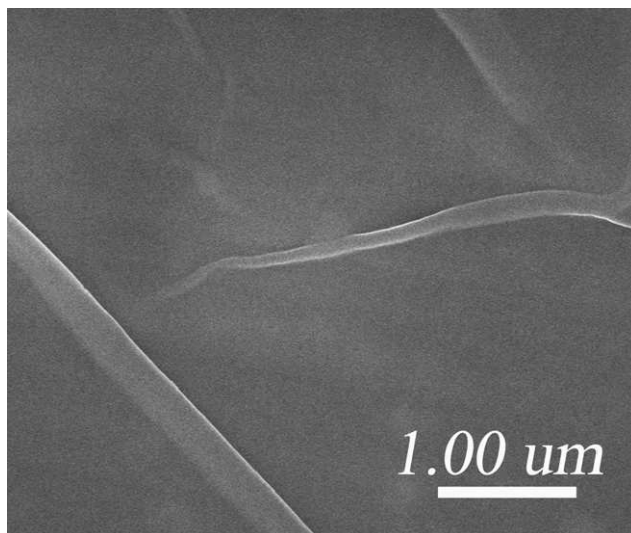


Figure S2 FESEM image of the rGO obtained from a hydrothermal treatment

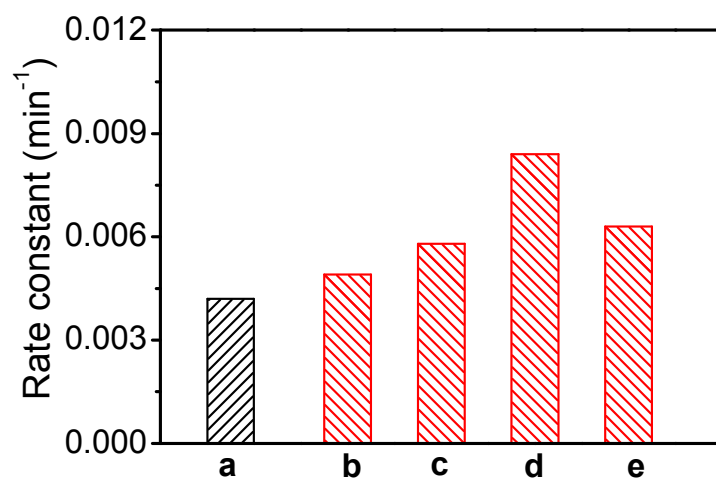


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